Inventor(s): David P. Bour et al.

PATENT APPLICATION

ATTORNEY DOCKET NO. 10031004-1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No.:		Examiner:				
Filing Date:	Herewith	Group Art Unit:				
Title:	BURIED HETEROSTRUCTUR	E DEVICE FABRICATED BY SINGLE STEP MOCVD				
PO Box 145	· ·					
Alexandria,	VA 22313-1450	ON DISCLOSURE STATEMENT				
Sir:	TINECTIVIATI	ON DISCLOSORE STATEWENT				
	ormation Disclosure Statement	So and asteroid				
		is submitted:				
	under 37 CFR 1.97(b), or (Within three months of filing nationalling date of first office action on the second sec	nal application; or date of entry of national application; or before the merits; whichever occurs last)				
	under 37 CFR 1.97(c) togethe () Statement under 37 CFR () a \$180.00 Processing fee (After the CFR 1.97 (b) time pe	1.97(e), or				
	under 37 CFR 1.97 (d) togeth () Statement under 37 CFR () a \$180.00 processing fee (Filed after final action or notice	1.97(e), and				
of this applica	ge to Deposit Account 50-107 ation, please charge any fee uant to 37 CFR 1.25.	78 the sum of $\$0.00$. At any time during the pendency s required or credit any overpayment to Deposit Account				
	Patent Application No	PTO 1449. References identified with an asterisk (*) were filed, now U. S. Patent No. eof are not included pursuant to the provisions of 37 CFR				
and other for individuals(s) attached shee foreign patent report or actio	eign language information lis designated in 37 CFR 1.56 (et, or where a foreign langua t office in a counterpart fore	ce of foreign language patents, foreign language publications sted on PTO Form 1449, as presently understood by the c) most knowledgeable about the content is given on the age patent is cited in a search report or other action by a sign application, an English language version of the search of relevance found by the foreign office is listed on form PTO				
"Express Mail" lal	bel no. EV 262 713 191 US	. Respectfully submitted,				
Date of [Deposit Feb. 25, 2004	David D. Plan and I				

By <u>Vinda () Ulmura</u>
Typed Name: Linda A. limura

I hereby certify that this is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR 1.10 on the date indicated above and is addressed to: Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450.

Attorney/Agent for Applicant(s)

Reg. No. 34,075

Ian Hardcastle

Date: Feb. 24, 2004

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Rev 05/03 (IDSXML)

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FORM PTO-1449			ATTY. DOCKET NO. S			SERIAL NO.					
				10031004-1							
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANT David P. Bour et al.							
										FILING DATE GROUP	
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				REFERENCE	DESIG	GNATION	U.S. PATE	NT DOC	JMENTS		
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EXAMINER Rev 5/90 (Form 3.05)